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UNIVERSITY OF
TECHNOLOGY

Preface

Citation for published version (APA):
Elam, J. W., Roozeboom, F., Delabie, A., Van Der Straten, O., Bent, S. F., De Gendt, S., & Londergan, A. (2010). Preface: Atomic Layer Deposition Applications 6 . *ECS Transactions*, *33*(2), iii.

Document status and date:
Published: 01/12/2010

Document Version:
Publisher's PDF, also known as Version of Record (includes final page, issue and volume numbers)

Please check the document version of this publication:

• A submitted manuscript is the version of the article upon submission and before peer-review. There can be important differences between the submitted version and the official published version of record. People interested in the research are advised to contact the author for the final version of the publication, or visit the DOI to the publisher's website.
• The final author version and the galley proof are versions of the publication after peer review.
• The final published version features the final layout of the paper including the volume, issue and page numbers.

Link to publication

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Download date: 08. Feb. 2024

PREFACE

The sixth symposium on Atomic Layer Deposition Applications was held October 10 to October 15, 2010 in Las Vegas, Nevada, as part of the 218th Meeting of The Electrochemical Society.

The continuously expanding realm of Atomic Layer Deposition (ALD) applications is the focus of this symposium. ALD can enable the precise deposition of ultra-thin, highly conformal coatings over complex, 3D topographies with controlled composition and properties. In its 6th successful year, this symposium has become a forum for sharing cutting edge research in the various areas where ALD is used. Emerging and non-mainstream ALD applications are also of special interest.

This issue of *ECS Transactions* contains 46 peer-reviewed papers presented at the symposium. The papers are organized into Chapters generally following the order in which they were presented. Featured ALD topics include surface engineering and nanofabrication, dielectrics for state-of-the-art transistors and capacitors, and the ALD of metals and metal nitrides. A number of papers report on progress in ALD equipment and precursor development. In addition, we held a session and panel discussion titled "Status and Challenges in Ultrafast ALD", a topic particularly suited for the emerging application of ALD for solar cell passivation.

We wish to thank the invited speakers for their outstanding contributions: Sonja Sioncke, *IMEC*; Brian Willis, *University of Connecticut*; Peide Ye, *Purdue University*; Peter Notten, *Eindhoven University of Technology*; Gregory Parsons, *North Carolina State University*; Francisco Zaera, *University of California, Riverside*; Cheol Seong Hwang, *Seoul National University*; Paul Ma, *Applied Materials*; John Abelson, *University of Illinois*; Elisabeth Blanquet, *CNRS*; Hyeongtag Jeon, *Hanyang University*; Alex Martinson, *Argonne National Laboratory*; Peter Carcia, *DuPont*; Paul Poodt, *TNO Science & Industry*; Ganesh Sundaram, *Cambridge NanoTech*; and Vladimir Kuznetsov, *Levitech BV*.

The financial support of the symposium sponsors is gratefully acknowledged: Air Liquide, Applied Materials, Cambridge NanoTech, Gelest, Qualcomm, and SAFC Hitech.

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